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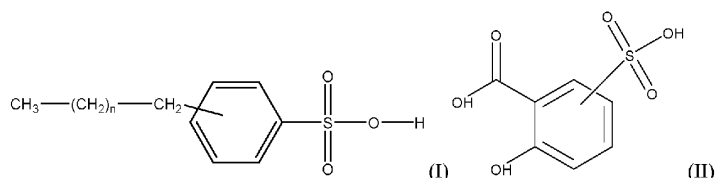
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(54) Title: PHOTORESIST REMOVER COMPOSITIONS



(57) Abstract: The present invention relates to a composition including a sulfonic acid selected from the group consisting of an alkyl-
benzenesulfonic acid having structure (I), or its hydrate (wherein n is an integer from 6 to 16), a sulfosalicylic acid having structure
(II), or its hydrate, and mixtures thereof and the solvent dipropylene glycol dimethyl ether [CAS registry number 111109-77-4] (III);

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